

Title (en)
ANTIREFLECTIVE COATINGS FOR VIA FILL AND PHOTOLITHOGRAPHY APPLICATIONS AND METHODS OF PREPARATION THEREOF

Title (de)
ANTIREFLEXBESCHICHTUNGEN ZUR KONTAKTLOCHFÜLLUNG UND PHOTOLITHOGRAPHIE-ANWENDUNGEN UND VERFAHREN ZU IHRER HERSTELLUNG

Title (fr)
REVETEMENTS ANTIREFLET DESTINES AU REMPLISSAGE DE TROUS D'INTERCONNEXION ET A DES APPLICATIONS DE PHOTOLITHOGRAPHIE ET LEURS PROCEDES DE PREPARATION

Publication
EP 1695142 A4 20070530 (EN)

Application
EP 04811280 A 20041117

Priority
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• US 71702803 A 20031118

Abstract (en)
[origin: WO2005049681A2] An absorbing composition is described herein that includes at least one inorganicbased compound, at least one absorbing compound, and at least one material modification agent. In addition, methods of making an absorbing composition are also described that includes: a) combining at least one inorganic-based compound, at least one absorbing compound, at least one material modification agent, an acid/water mixture, and one or more solvents to form a reaction mixture; and b) allowing the reaction mixture to form the absorbing composition at room temperature. Another method of making an absorbing composition includes: a) combining at least one inorganic-based compound, at least one absorbing compound, at least one material modification agent, an acid/water mixture, and one or more solvents to form a reaction mixture; and b) heating the reaction mixture to form the absorbing composition. Yet another method of making an absorbing composition is described that includes: a) combining at least one inorganic-based compound, at least one absorbing compound, at least one material modification agent, and one or more solvents to form a reaction mixture, wherein the at least one material modification agent comprises at least one acid and water; and b) heating the reaction mixture to form an absorbing material, a coating or a film. In other methods of making an absorbing composition described herein, those methods include: a) combining at least one inorganic-based compound, at least one absorbing compound, at least one material modification agent, and one or more solvents to form a reaction mixture, wherein the at least one material modification agent comprises at least one acid and water; and b) allowing the reaction mixture to form an absorbing material, a coating or a film.

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Citation (search report)
• [X] WO 03044078 A1 20030530 - HONEYWELL INT INC [US], et al
• [X] WO 03044077 A1 20030530 - HONEYWELL INT INC [US], et al
• [X] WO 03044600 A1 20030530 - HONEYWELL INT INC [US], et al
• [A] WO 03044079 A1 20030530 - HONEYWELL INT INC [US], et al
• See references of WO 2005049681A2

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DOCDB simple family (publication)
WO 2005049681 A2 20050602; WO 2005049681 A3 20060420; CN 103627316 A 20140312; CN 103627316 B 20160803; CN 1902546 A 20070124; CN 1902546 B 20121114; EP 1695142 A2 20060830; EP 1695142 A4 20070530; EP 1695142 B1 20190731; JP 2007520737 A 20070726; JP 2012025957 A 20120209; JP 4857119 B2 20120118; JP 5467082 B2 20140409; KR 101324022 B1 20131101; KR 20060099532 A 20060919; KR 20120115432 A 20121017; TW 200538511 A 20051201; TW I374914 B 20121021; US 2005171277 A1 20050804; US 2012001135 A1 20120105; US 8053159 B2 20111108; US 8992806 B2 20150331

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